


In th Claims

CLAIMS

Claims 1-4 (Cancelled).

5. (Original) A method of forming an electrical connection comprising:  
forming a diffusion region in semiconductive material, the diffusion region  
having an outer surface;

 forming a conductive line laterally spaced from the semiconductive material  
and diffusion region, a predominate portion of the conductive line being disposed  
elevationally below the diffusion region outer surface; and

interconnecting the conductive line and the diffusion region with electrically  
conductive material.

6. (Original) The method of claim 5, wherein the interconnecting the  
conductive line and the diffusion region comprises forming the electrically  
conductive material over both the conductive line and the diffusion region.

7. (Original) The method of claim 5, wherein the forming of the conductive line comprises:

forming an isolation oxide region laterally adjacent the semiconductive material, the oxide region having a lateral width;

removing a portion of the isolation oxide intermediate the lateral width; and

replacing at least some of the removed isolation oxide with electrically conductive material.

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8. (Original) The method of claim 5, wherein the forming of the conductive line comprises:

forming an isolation oxide region laterally adjacent the semiconductive material, the oxide region having a lateral width;

removing a portion of the isolation oxide intermediate the lateral width and to a greater degree in an elevationally downward direction than a laterally outward direction; and

replacing at least some of the removed isolation oxide with electrically conductive material.

9. (Original) The method of claim 5, wherein the forming of the conductive line comprises:

forming an isolation oxide region laterally adjacent the semiconductive material, the oxide region having a first lateral width;

B2 removing a portion of the isolation oxide at least intermediate the lateral width;

forming oxide material within the first lateral width and to a degree sufficient to occupy less than the first lateral width and to define a second lateral width; and

replacing at least some of the removed isolation oxide with electrically conductive material.

[Claims 10-39 (Cancelled).]

40. (New) A method of forming an electrical connection comprising:

forming a conductive node in semiconductive material;

forming a conductive line laterally spaced from the semiconductive material and conductive node, a predominate portion of the conductive line being disposed elevationally below the conductive node; and

interconnecting the conductive line and the conductive node with electrically conductive material.

41. (New) The method of claim 40, wherein the forming of the conductive node comprises forming a source/drain region.

42. (New) The method of claim 40, wherein the interconnecting of the conductive line and the conductive node comprises forming the electrically conductive material over both the conductive line and the conductive node.

B2 43. (New) The method of claim 40, wherein the forming of the conductive line and the electrically conductive material comprises forming both from the same material.

44. (New) The method of claim 40, wherein the forming of the conductive line and the electrically conductive material comprises forming both from different material.

45. (New) The method of claim 40 further comprising forming insulating material between the conductive line and the conductive node.

46. (New) The method of claim 40 further comprising forming insulating material between the conductive line and the semiconductive material.

47. (New) The method of claim 40 further comprising forming oxide material between the conductive line and the semiconductive material.

48. (New) The method of claim 40, wherein the forming of the conductive line and the electrically conductive material comprises forming both from undoped polysilicon, and further comprising implanting dopants into the undoped polysilicon.

49. (New) The method of claim 40, wherein the forming of the conductive line and the electrically conductive material comprises forming both from doped polysilicon.

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50. (New) The method of claim 40, wherein the forming of the conductive line and the electrically conductive material comprises forming both from refractory metals.

51. (New) The method of claim 40, wherein the forming of the conductive line comprises:

forming an isolation oxide region laterally adjacent the semiconductive material, the oxide region having a lateral width;

removing a portion of the isolation oxide intermediate the lateral width; and

replacing at least some of the removed isolation oxide with electrically conductive material.

52. (New) The method of claim 40, wherein the forming of the conductive line comprises:

forming an isolation oxide region laterally adjacent the semiconductive material, the oxide region having a lateral width;

removing a portion of the isolation oxide intermediate the lateral width and to a greater degree in an elevationally downward direction than a laterally outward direction; and

replacing at least some of the removed isolation oxide with electrically conductive material.

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53. (New) The method of claim 40, wherein the forming of the conductive line comprises:

forming an isolation oxide region laterally adjacent the semiconductive material, the oxide region having a first lateral width;

removing a portion of the isolation oxide at least intermediate the lateral width;

forming oxide material within the first lateral width and to a degree sufficient to occupy less than the first lateral width and to define a second lateral width; and

replacing at least some of the removed isolation oxide with electrically conductive material.